TSMC-01-809



January 9, 2002

To: Commissioner Tatents and Trademarks

Washington, D.C. 20231

Fr: George O. Saile, Reg. No. 19,572

20 McIntosh Drive

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TC 1700

Subject:

Serial No. 09/993,069 11/14/01

Chun-Hung Kung

METHOD OF REPAIRING PSM TO KEEP NORMAL TRANSMISSION RATE AND PHASE ANGLE

Grp. Art Unit: 1756

INFORMATION DISCLOSURE STATEMENT

Enclosed is Form PTO-1449, Information Disclosure Citation In An Application.

The following Patents and/or Publications are submitted to comply with the duty of disclosure under CFR 1.97-1.99 and 37 CFR 1.56. Copies of each document is included herewith.

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to: Commissioner of Patents and Trademarks, Washington, D.C. 20231, on January 21, 2002.

Stephen B. Ackerman, Reg.# 37761

Signature/Date

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- U.S. Patent 5,965,303 to Huang, "Method of Fabricating a Phase Shift Mask Utilizing a Defect Repair Machine," discloses a method for fabricating a phase shift mask utilizing a defect repair tool.
- U.S. Patent 6,207,328 to Lin, "Method of Forming a Phase Shift Mask," discloses a method for forming a phase shift mask.
- U.S. Patent 5,382,484 to Hosono, "Method of Correcting Defects in the Pattern of Phase Shift Mask," discloses a method to correct defects in a PSM including Ga stains.
- U.S. Patent 6,042,738 to Casey, Jr. et al., "Pattern Film Repair Using a Focused Particle Beam System," discloses a pattern film repair method using a focused particle beam system.

Sincerely

Stephen B. Ackerman,

Reg. No. 37761